

Dry Etch

Plasma / Reactive Ion Etch

[LAM 4600 AI Etcher](#)

- Used for dry etching of aluminum metal layers

[LAM 490 AutoEtch](#)

- Used for plasma etching of silicon and silicon nitride

[Trion Etcher](#)

- Used for reactive ion etching of silicon oxide

[AME P5000 Chamber C](#)

- Used for reactive ion etching of silicon dioxide

Oxygen Plasma Strippers

Other Etchers

[Xactic XeF2 Etcher](#)

- Used for surface release etching silicon

[STS ASE Deep Si Etcher](#)

- Used for deep anisotropic etches of Si

Other Information

[Dry Etch Process Information](#)